

ABSTRACT

A method for fabricating a mask which includes a printable contact and/or line area which is aligned with a phase-shifter. The method includes preparing a mask-in-process comprising a substrate underlying a first layer, an opaque layer overlying the first layer, and a first resist material overlying the opaque layer, and subjecting the mask-in-process to a plurality of exposures and at least one etching to create a phase-shifter and to open a printable contact and/or line area surrounded by a second resist material, wherein the printable contact and/or line area is aligned with the phase-shifter.

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